in-process substrate, and relatively moving said in-process substrate or said dropping section, wherein

relative movement between said in-process substrate and said dropping section means rotating said substrate and relatively moving said dropping section from an inner periphery of said substrate toward an outer periphery of said substrate for spirally dropping said liquid on said in-process substrate;

rotational frequency w for said substrate is decreased and feed rate v for said liquid from said dropping section is increased so that the liquid dropped from said dropping section on said in-process substrate stays at dropped position in accordance with relative movement of said dropping section from the inner periphery of said in-process substrate toward the outer periphery;

otherwise,

relative movement between said in-process substrate and said dropping section means rotating said substrate and relatively moving said dropping section from an outer periphery of said substrate toward an inner periphery of said substrate for spirally dropping said liquid on said in-process substrate; and

rotational frequency w for said substrate is increased and feed rate v for said liquid from said dropping section is decreased so that the liquid dropped from said dropping section on said in-process substrate stays at dropped position in accordance with relative movement of said dropping section from the outer periphery of said in-process substrate toward the inner periphery.

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2. (Amended) The film formation method according to claim 1, wherein when said dropping section is positioned to distance r from a center of said in-process substrate, feed rate v for said liquid from said dropping section is determined in accordance with rotational frequency w for said in-process substrate so that a constant value is maintained for the product of rotational frequency w and feed rate v of said substrate support.

4. (Amended) The film formation method according to claim 3 , wherein when said in-process substrate is a disk-shaped substrate with radius R (mm), said dropping section drops liquid at the outmost periphery of said substrate and a rotational frequency (rpm) for said substrate is smaller than the square root of 1,000,000/R.

Information Disclosure Statement

The Examiner alleged that the previously filed Information Disclosure Statement filed on April 26, 2001 failed to comply with the requirements of 37 C.F.R. §§ 1.98(a)(2) & (a)(3).

Specifically, the Examiner was unable to find copies of the document listed in the section entitled "Other Documents." Applicants enclose a duplicate copy of each of the documents listed in that section. Applicants respectfully request that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the previously submitted PTO-1449 form.

The Examiner also stated that the Information Disclosure Statement filed on April 26, 2001 does not include a concise explanation of the relevance of each patent listed

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